

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID: SSSPTA1752YXC

PASSWORD:

TERMINAL (ENTER 1, 2, 3, OR ?):2

* * * * * * * * * * * Welcome to STN International * * * * * * * * * * *

| | | |
|--------------|----|---|
| NEWS | 1 | Web Page URLs for STN Seminar Schedule - N. America |
| NEWS | 2 | "Ask CAS" for self-help around the clock |
| NEWS | 3 | May 12 EXTEND option available in structure searching |
| NEWS | 4 | May 12 Polymer links for the POLYLINK command completed in REGISTRY |
| NEWS | 5 | May 27 New UPM (Update Code Maximum) field for more efficient patent SDIs in CAplus |
| NEWS | 6 | May 27 CAplus super roles and document types searchable in REGISTRY |
| NEWS | 7 | Jun 28 Additional enzyme-catalyzed reactions added to CASREACT |
| NEWS | 8 | Jun 28 ANTE, AQUALINE, BIOENG, CIVILENG, ENVIROENG, MECHENG, and WATER from CSA now available on STN(R) |
| NEWS | 9 | Jul 12 BEILSTEIN enhanced with new display and select options, resulting in a closer connection to BABS |
| NEWS | 10 | Jul 30 BEILSTEIN on STN workshop to be held August 24 in conjunction with the 228th ACS National Meeting |
| NEWS | 11 | AUG 02 IFIPAT/IFIUDB/IFICDB reloaded with new search and display fields |
| NEWS | 12 | AUG 02 CAplus and CA patent records enhanced with European and Japan Patent Office Classifications |
| NEWS | 13 | AUG 02 STN User Update to be held August 22 in conjunction with the 228th ACS National Meeting |
| NEWS | 14 | AUG 02 The Analysis Edition of STN Express with Discover! (Version 7.01 for Windows) now available |
| NEWS | 15 | AUG 04 Pricing for the Save Answers for SciFinder Wizard within STN Express with Discover! will change September 1, 2004 |
| NEWS | 16 | AUG 27 BIOCOMMERCE: Changes and enhancements to content coverage |
| NEWS | 17 | AUG 27 BIOTECHABS/BIOTECHDS: Two new display fields added for legal status data from INPADOC |
| NEWS | 18 | SEP 01 INPADOC: New family current-awareness alert (SDI) available |
| NEWS | 19 | SEP 01 New pricing for the Save Answers for SciFinder Wizard within STN Express with Discover! |
| NEWS | 20 | SEP 01 New display format, HITSTR, available in WPIDS/WPINDEX/WPIX |
| NEWS | 21 | SEP 14 STN Patent Forum to be held October 13, 2004, in Iselin, NJ |
| NEWS EXPRESS | | JULY 30 CURRENT WINDOWS VERSION IS V7.01, CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP), AND CURRENT DISCOVER FILE IS DATED 11 AUGUST 2004 |
| NEWS HOURS | | STN Operating Hours Plus Help Desk Availability |
| NEWS INTER | | General Internet Information |
| NEWS LOGIN | | Welcome Banner and News Items |
| NEWS PHONE | | Direct Dial and Telecommunication Network Access to STN |
| NEWS WWW | | CAS World Wide Web Site (general information) |

Enter NEWS followed by the item number or name to see news on that specific topic.

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* * * * * * * * * * * * * * * * * STN Columbus * * * * * * * * * * * * * * * * *

FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004

=> file reg
COST IN U.S. DOLLARS
SINCE FILE
ENTRY
TOTAL
SESSION
FULL ESTIMATED COST 0.21 0.21

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2004 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file
provided by InfoChem.

STRUCTURE FILE UPDATES: 16 SEP 2004 HIGHEST RN 746205-18-5
DICTIONARY FILE UPDATES: 16 SEP 2004 HIGHEST RN 746205-18-5

TSCA INFORMATION NOW CURRENT THROUGH MAY 21, 2004

Please note that search-term pricing does apply when
conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more
information enter HELP PROP at an arrow prompt in the file or refer
to the file summary sheet on the web at:
<http://www.cas.org/ONLINE/DBSS/registryss.html>

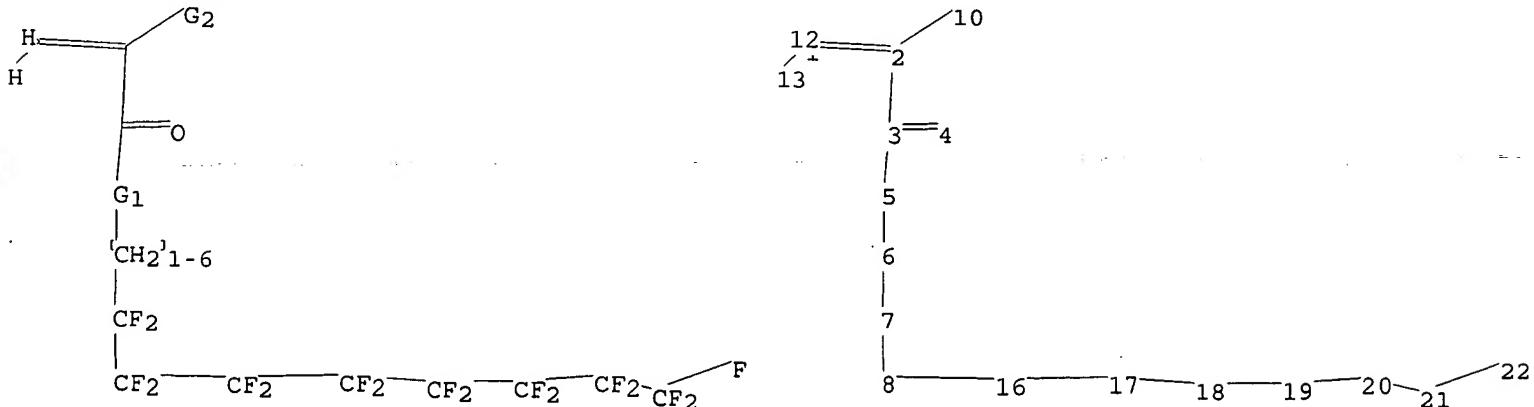
=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END) :end

=> screen 970 AND 2067

L1 SCREEN CREATED

=>
Uploading C:\Program Files\Stnexp\Queries\10642576-3.str



chain nodes :

1 2 3 4 5 6 7 8 10 12 13 16 17 18 19 20 21 22

chain bonds :

1-2 1-12 1-13 2-3 2-10 3-4 3-5 5-6 6-7 7-8 8-16 16-17 17-18 18-19 19-20 20-21

21-22

exact/norm bonds :
2-10 3-4 3-5 5-6
exact bonds :
1-2 1-12 1-13 2-3 6-7 7-8 8-16 16-17 17-18 18-19 19-20 20-21 21-22

G1:O,S,N

G2:CH2,H

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 12:CLASS
13:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS 20:CLASS 21:CLASS 22:CLASS

L2 STRUCTURE UPLOADED

=> que L2 AND L1

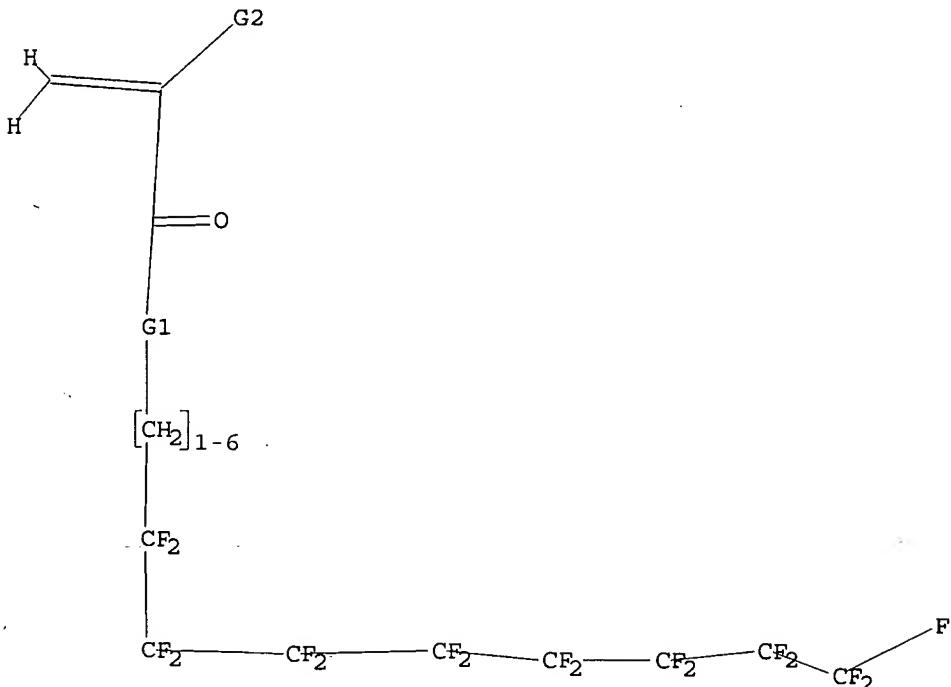
L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 970 AND 2067

L2 STR



G1 O,S,N

G2 CH2,H

Structure attributes must be viewed using STN Express query preparation.

L3 QUE ABB=ON PLU=ON L2 AND L1

=> s 13 sss sam

SAMPLE SEARCH INITIATED 20:40:00 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 350 TO ITERATE

100.0% PROCESSED 350 ITERATIONS
INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)
SEARCH TIME: 00.00.01

50 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 5878 TO 8122
PROJECTED ANSWERS: 2990 TO 4648

L4 50 SEA SSS SAM L2 AND L1

=>Testing the current file.... screen

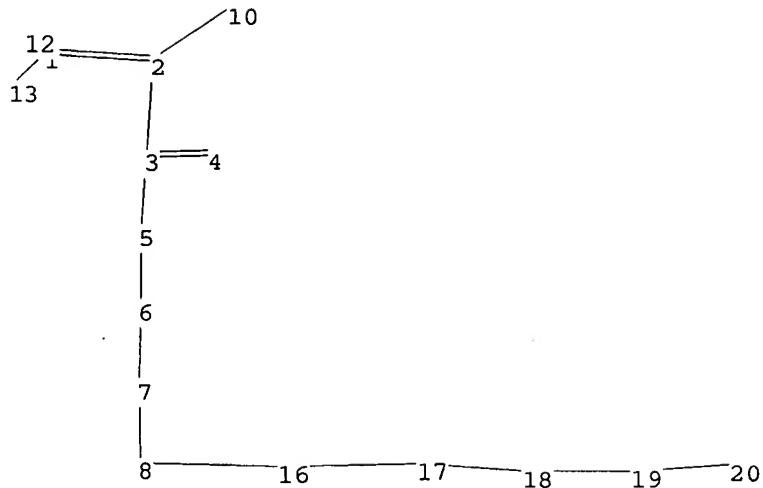
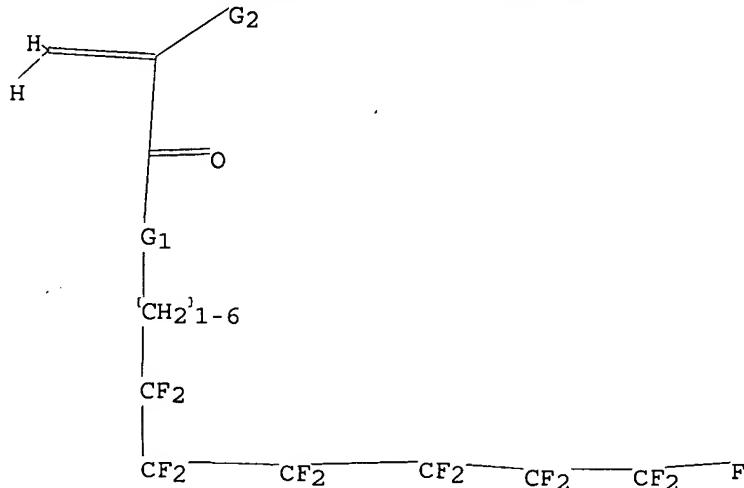
ENTER SCREEN EXPRESSION OR (END) :end

=> screen 970 AND 2067

L5 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10642576-2.str



chain nodes :

1 2 3 4 5 6 7 8 10 12 13 16 17 18 19 20

chain bonds :

1-2 1-12 1-13 2-3 2-10 3-4 3-5 5-6 6-7 7-8 8-16 16-17 17-18 18-19 19-20

exact/norm bonds :

2-10 3-4 3-5 5-6

exact bonds :

1-2 1-12 1-13 2-3 6-7 7-8 8-16 16-17 17-18 18-19 19-20

G1:O,S,N

G2:CH₂,H

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 12:CLASS
13:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS 20:CLASS

L6 STRUCTURE UPLOADED

=> que L6 AND L5

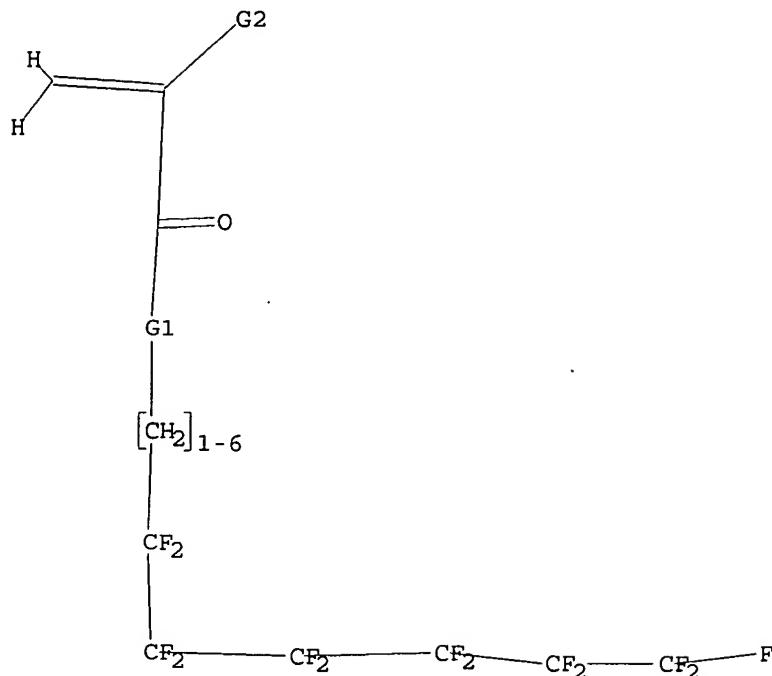
L7 QUE L6 AND L5

=> d

L7 HAS NO ANSWERS

L5 SCR 970 AND 2067

L6 STR



G1 O, S, N

G2 CH₂, H

Structure attributes must be viewed using STN Express query preparation.

L7 QUE ABB=ON PLU=ON L6 AND L5

=> s 17 sss sam
SAMPLE SEARCH INITIATED 20:40:33 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 415 TO ITERATE

100.0% PROCESSED 415 ITERATIONS 39 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 7078 TO 9522
PROJECTED ANSWERS: 406 TO 1154

L8 39 SEA SSS SAM L6 AND L5

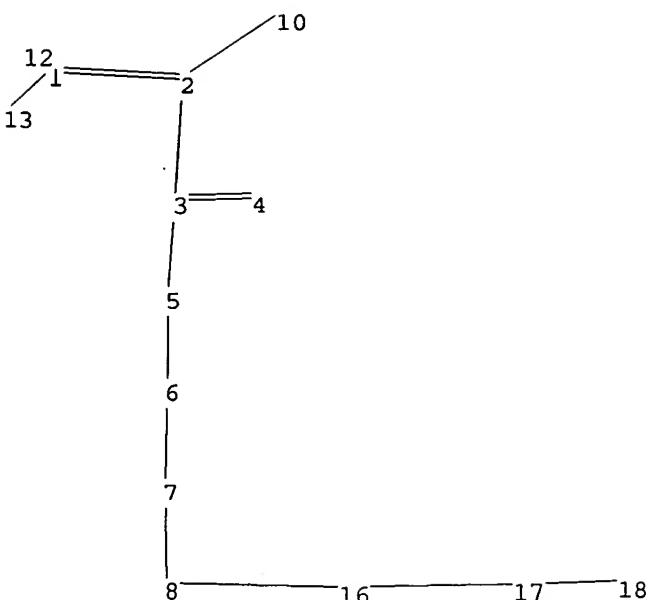
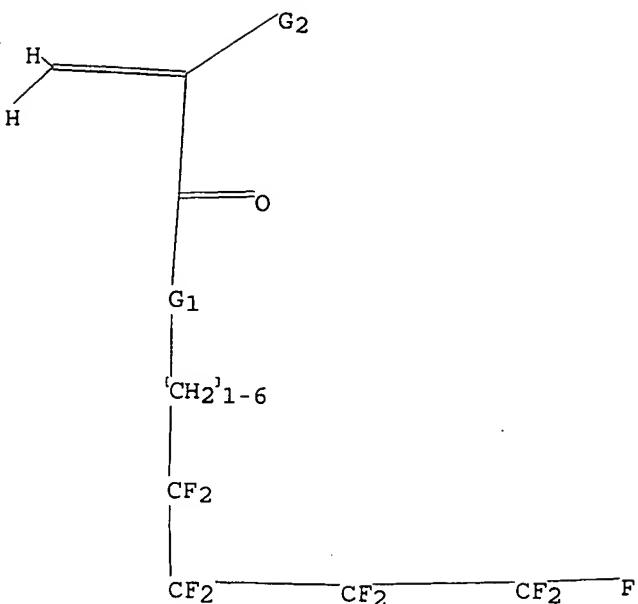
=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L9 SCREEN CREATED

=>
Uploading C:\Program Files\Stnexp\Queries\10642576-1.str



chain nodes :

1 2 3 4 5 6 7 8 10 12 13 16 17 18

chain bonds :

1-2 1-12 1-13 2-3 2-10 3-4 3-5 5-6 6-7 7-8 8-16 16-17 17-18

exact/norm bonds :

2-10 3-4 3-5 5-6

exact bonds :

1-2 1-12 1-13 2-3 6-7 7-8 8-16 16-17 17-18

G1:O,S,N

G2:CH2,H

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 12:CLASS
13:CLASS 16:CLASS 17:CLASS 18:CLASS

L10 STRUCTURE UPLOADED

=> que L10 AND L9

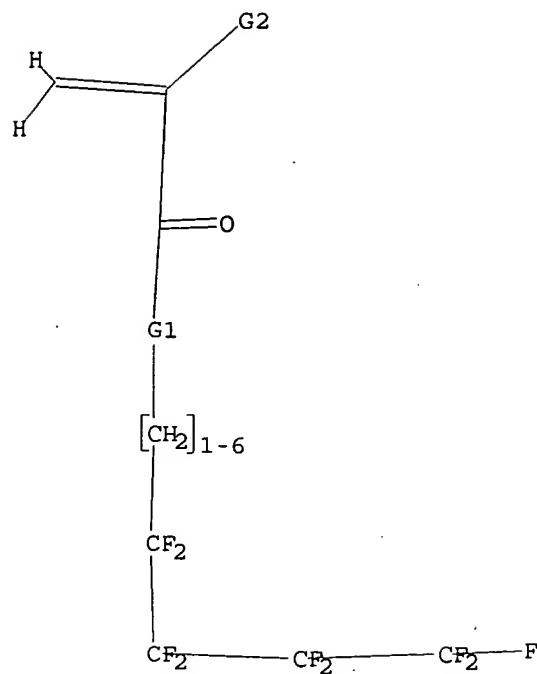
L11 QUE L10 AND L9

=> d

L11 HAS NO ANSWERS

L9 SCR 970 AND 2067

L10 STR



G1 O, S, N

G2 CH₂, H

Structure attributes must be viewed using STN Express query preparation.

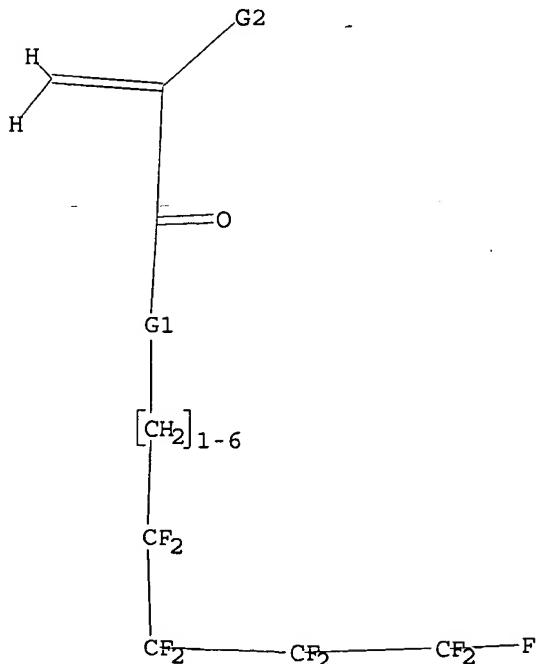
L11 QUE ABB=ON PLU=ON L10 AND L9

=> d

L11 HAS NO ANSWERS

L9 SCR 970 AND 2067

L10 STR



G1 O, S, N

G2 CH₂, H

Structure attributes must be viewed using STN Express query preparation.

L11

QUE ABB=ON PLU=ON L10 AND L9

=> s 111 sss sam
SAMPLE SEARCH INITIATED 20:41:17 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 458 TO ITERATE

100.0% PROCESSED 458 ITERATIONS 19 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 7877 TO 10443
PROJECTED ANSWERS: 119 TO 641

L12 19 SEA SSS SAM L10 AND L9

=> d his

(FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

L1 SCREEN 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 50 S L3 SSS SAM
L5 SCREEN 970 AND 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 39 S L7 SSS SAM
L9 SCREEN 970 AND 2067
L10 STRUCTURE UPLOADED
L11 QUE L10 AND L9
L12 19 S L11 SSS SAM

=> s 14 or 18 or 112

L13 102 L4 OR L8 OR L12

=> FIL HCAPLUS, CAPLUS, USPATFULL

| COST IN U.S. DOLLARS | SINCE FILE ENTRY | TOTAL SESSION |
|----------------------|------------------|---------------|
| FULL ESTIMATED COST | 1.68 | 1.89 |

FILE 'HCAPLUS' ENTERED AT 20:41:37 ON 17 SEP 2004

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
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COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 20:41:37 ON 17 SEP 2004

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

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FILE 'USPATFULL' ENTERED AT 20:41:37 ON 17 SEP 2004
CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 113

L14 238 L13

=> duplicates remove 114
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L14

L15 130 DUPLICATE REMOVE L14 (108 DUPLICATES REMOVED)

=> s oxime sulfonate
L16 301 OXIME SULFONATE

=> s 116 and 114

=> d 117 1-3 ibib hitstr

L17 ANSWER 1 OF 3 HCPLUS COPYRIGHT 2004 ACS on STN
 ACCESSION NUMBER: 2004:200910 HCPLUS
 DOCUMENT NUMBER: 140:243596
 TITLE: Chemically amplified positive photoresists suppressing development defects
 INVENTOR(S): Momota, Atsushi
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---------------|------|----------|-----------------|------------|
| JP 2004078105 | A2 | 20040311 | JP 2002-241946 | 20020822 |
| US 2004048190 | A1 | 20040311 | US 2003-642576 | 20030819 |
| | | | JP 2002-241946 | A 20020822 |

PRIORITY APPLN. INFO.: OTHER SOURCE(S): MARPAT 140:243596

IT 668476-75-3P

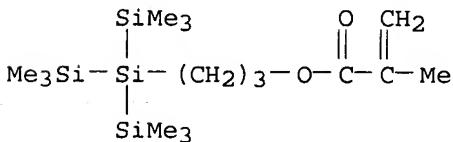
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (surfactants; chemical amplified pos. photoresists containing fluoroalkyl acrylate-polymerized surfactants and suppressing development defects)

RN 668476-75-3 HCPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 3,3,4,4,5,5,6;6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, α -(2-methyl-1-oxo-2-propenyl)- ω -methoxypoly(oxy-1,2-ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

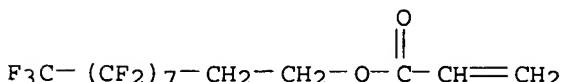
CM 1

CRN 114349-68-7
 CMF C16 H38 O2 Si4



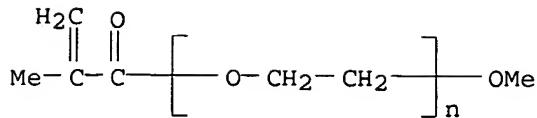
CM 2

CRN 27905-45-9
 CMF C13 H7 F17 O2



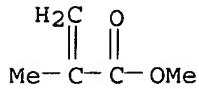
CM 3

CRN 26915-72-0
 CMF (C2 H4 O)n C5 H8 O2
 CCI PMS



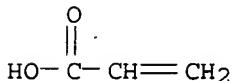
CM 4

CRN 80-62-6
CMF C5 H8 O2



CM 5

CRN 79-10-7
CMF C3 H4 O2



L17 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER:

2004:200910 CAPLUS

DOCUMENT NUMBER:

140:243596

TITLE: Chemically amplified positive photoresists suppressing development defects

INVENTOR(S): Momota, Atsushi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---------------|------|----------|-----------------|------------|
| JP 2004078105 | A2 | 20040311 | JP 2002-241946 | 20020822 |
| US 2004048190 | A1 | 20040311 | US 2003-642576 | 20030819 |
| | | | JP 2002-241946 | A 20020822 |

PRIORITY APPLN. INFO.: MARPAT 140:243596

OTHER SOURCE(S):

MARPAT 140:243596

IT 668476-75-3P

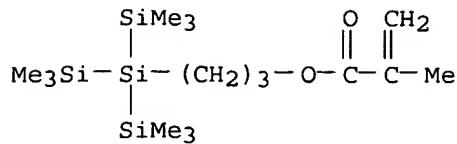
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (surfactants; chemical amplified pos. photoresists containing fluoroalkyl acrylate-polymerized surfactants and suppressing development defects)

RN 668476-75-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, α -(2-methyl-1-oxo-2-propenyl)- ω -methoxypoly(oxy-1,2-ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

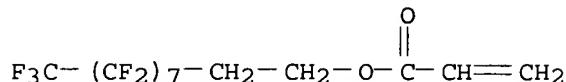
CM 1

CRN 114349-68-7
CMF C16 H38 O2 Si4



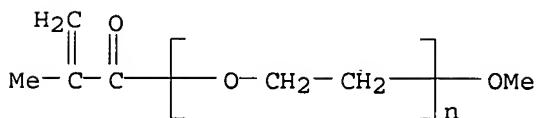
CM 2

CRN 27905-45-9
 CMF C13 H7 F17 O2



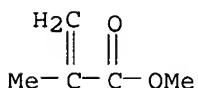
CM 3

CRN 26915-72-0
 CMF (C₂ H₄ O)_n C₅ H₈ O₂
 CCI PMS



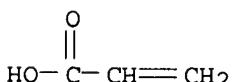
CM 4

CRN 80-62-6
 CMF C₅ H₈ O₂



CM 5

CRN 79-10-7
 CMF C₃ H₄ O₂



L17 ANSWER 3 OF 3 USPATFULL on STN

ACCESSION NUMBER: 2004:63672 USPATFULL
 TITLE: Positive photoresist composition
 INVENTOR(S): Momota, Makoto, Shizuoka, JAPAN
 PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

| PATENT INFORMATION: | NUMBER | KIND | DATE |
|---------------------|---------------|------|----------|
| | US 2004048190 | A1 | 20040311 |

APPLICATION INFO.: US 2003-642576 A1 20030819 (10)

| | NUMBER | DATE |
|-----------------------|--|----------|
| PRIORITY INFORMATION: | JP 2002-241946 | 20020822 |
| DOCUMENT TYPE: | Utility | |
| FILE SEGMENT: | APPLICATION | |
| LEGAL REPRESENTATIVE: | SUGHRUE MION, PLLC, 2100 PENNSYLVANIA AVENUE, N.W.,
WASHINGTON, DC. 20037 | |

NUMBER OF CLAIMS: 8

EXEMPLARY CLAIM:

LINE COUNT: 1349

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 668476-75-3P

(surfactants; chemical amplified pos. photoresists containing fluoroalkyl acrylate-polymerized surfactants and suppressing development defects)

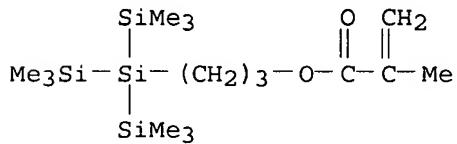
RN 668476-75-3 USPATFULL

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate,
 α -(2-methyl-1-oxo-2-propenyl)- ω -methoxypoly(oxy-1,2-
ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-
bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA
INDEX NAME)

CM 1

CRN 114349-68-7

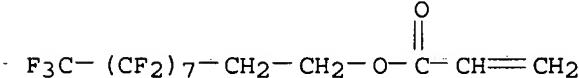
CMF C16 H38 O2 Si4



CM 2

CRN 27905-45-9

CMF C13 H7 F17 O2

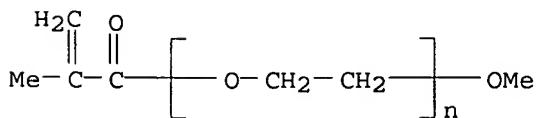


CM 3

CRN 26915-72-0

CMF (C₂ H₄ O)_n C₅ H₈ O₂

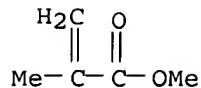
CCI PMS



CM 4

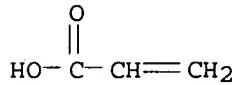
CRN 80-62-6

CMF C5 H8 O2



CM 5

CRN 79-10-7
CMF C3 H4 O2



=> d his

(FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

L1 SCREEN 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 50 S L3 SSS SAM
L5 SCREEN 970 AND 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 39 S L7 SSS SAM
L9 SCREEN 970 AND 2067
L10 STRUCTURE UPLOADED
L11 QUE L10 AND L9
L12 19 S L11 SSS SAM
L13 102 S L4 OR L8 OR L12

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 20:41:37 ON 17 SEP 2004

L14 238 S L13
L15 130 DUPLICATE REMOVE L14 (108 DUPLICATES REMOVED)
L16 301 S OXIME SULFONATE
L17 3 S L16 AND L14

=> s l14 and (resist or photoresist)
L18 9 L14 AND (RESIST OR PHOTORESIST)

=> s l18 not l17
L19 6 L18 NOT L17

=> d l19 1-6 ibib hitstr

L19 ANSWER 1 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN
 ACCESSION NUMBER: 2003:735196 HCAPLUS
 DOCUMENT NUMBER: 139:267983
 TITLE: Positive-working photoresist composition
 containing polymer with fluoro-aliphatic group
 INVENTOR(S): Fujimori, Toru
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------|-------|-------|-----------------|-------|
| ----- | ----- | ----- | ----- | ----- |

JP 2003262952

A2 20030919

JP 2002-65444

20020311

PRIORITY APPLN. INFO.:

JP 2002-65444

20020311

IT 602299-35-4

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)
 (surfactant; pos. photoresist composition containing polymer with
 fluoro-aliphatic group)

RN 602299-35-4 HCPLUS

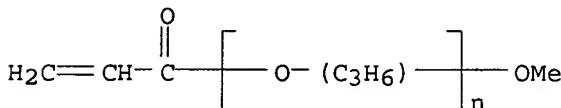
CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-
 heptadecafluorodecyl ester, polymer with α -(1-oxo-2-propenyl)-
 ω -hydroxypoly(oxy-1,2-ethanediyl) and α -(1-oxo-2-propenyl)-
 ω -methoxypoly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

CM 1

CRN 83844-54-6

CMF (C₃ H₆ O)_n C₄ H₆ O₂

CCI IDS, PMS

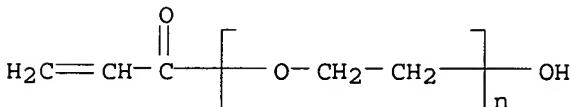


CM 2

CRN 26403-58-7

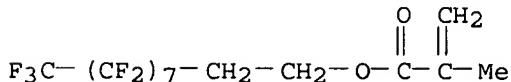
CMF (C₂ H₄ O)_n C₃ H₄ O₂

CCI PMS



CM 3

CRN 1996-88-9

CMF C₁₄ H₉ F₁₇ O₂

L19 ANSWER 2 OF 6 HCPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1998:335551 HCPLUS

DOCUMENT NUMBER: 129:54119

TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their
 (polymer) films, and photoresists using the
 same

INVENTOR(S): Miyashita, Tokuji

PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.

KIND DATE

APPLICATION NO.

DATE

 JP 10139747 A2 19980526 JP 1996-312953 19961108
 PRIORITY APPLN. INFO.: MARPAT 129:54119 JP 1996-312953 19961108
 OTHER SOURCE(S) :
 IT 208589-71-3P

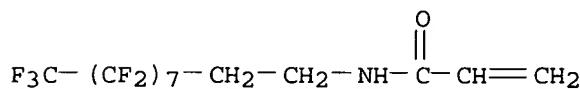
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (LB films of N-polyfluoroalkyl(meth)acrylamides and their polymers with good water repellency, photosensitivity, and slip property)

RN 208589-71-3 CAPLUS

CN 2-Propenamide, N-(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 208589-64-4
 CMF C13 H8 F17 N O



L19 ANSWER 3 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2003:735196 CAPLUS

DOCUMENT NUMBER: 139:267983

TITLE: Positive-working photoresist composition containing polymer with fluoro-aliphatic group

INVENTOR(S): Fujimori, Toru

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|------|----------|-----------------|----------|
| JP 2003262952 | A2 | 20030919 | JP 2002-65444 | 20020311 |
| PRIORITY APPLN. INFO.: | | | JP 2002-65444 | 20020311 |

IT 602299-35-4

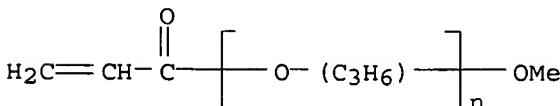
RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)
 (surfactant; pos. photoresist composition containing polymer with fluoro-aliphatic group)

RN 602299-35-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl ester, polymer with α -(1-oxo-2-propenyl)- ω -hydroxypoly(oxy-1,2-ethanediyl) and α -(1-oxo-2-propenyl)- ω -methoxypoly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

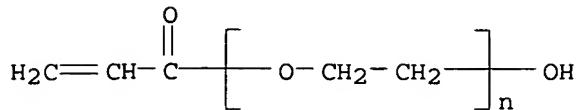
CM 1

CRN 83844-54-6
 CMF (C₃H₆O)_n C₄H₆O₂
 CCI IDS, PMS



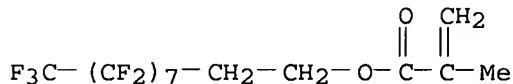
CM 2

CRN 26403-58-7
CMF (C₂ H₄ O)_n C₃ H₄ O₂
CCI PMS



CM 3

CRN 1996-88-9
CMF C₁₄ H₉ F₁₇ O₂



L19 ANSWER 4 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1998:335551 CAPLUS
DOCUMENT NUMBER: 129:54119
TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their (polymer) films, and photoresists using the same
INVENTOR(S): Miyashita, Tokuji
PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|------|----------|-----------------|----------|
| JP 10139747 | A2 | 19980526 | JP 1996-312953 | 19961108 |
| PRIORITY APPLN. INFO.: | | | JP 1996-312953 | 19961108 |

OTHER SOURCE(S): MARPAT 129:54119

IT 208589-71-3P

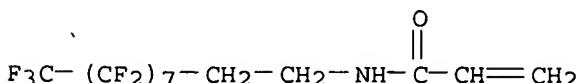
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(LB films of N-polyfluoroalkyl(meth)acrylamides and their polymers with good water repellency, photosensitivity, and slip property)

RN 208589-71-3 CAPLUS

CN 2-Propenamide, N-(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 208589-64-4
CMF C₁₃ H₈ F₁₇ N O



L19 ANSWER 5 OF 6 USPATFULL on STN
ACCESSION NUMBER: 2002:59638 USPATFULL
TITLE: Top coating for synthetic leathers

INVENTOR(S) :

Huang, Hsu-Nan, Newark, DE, UNITED STATES

NUMBER KIND DATE

PATENT INFORMATION: US 2002033468 A1 20020321
APPLICATION INFO.: US 2001-970478 A1 20011004 (9)
RELATED APPLN. INFO.: Division of Ser. No. US 2000-495132, filed on 31 Jan 2000, PENDING

NUMBER DATE

PRIORITY INFORMATION: US 1999-123601P 19990310 (60)
DOCUMENT TYPE: Utility
FILE SEGMENT: APPLICATION
LEGAL REPRESENTATIVE: E I DU PONT DE NEMOURS AND COMPANY, LEGAL DEPARTMENT - PATENTS, 1007 MARKET STREET, WILMINGTON, DE, 19898

NUMBER OF CLAIMS: 11

EXEMPLARY CLAIM: 1

LINE COUNT: 1042

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 292849-59-3P

(water- and oil-repellent coating compns. for synthetic grain leather)

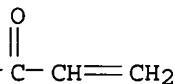
RN 292849-59-3 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, N-(hydroxymethyl)-2-propenamide and α -(2-methyl-1-oxo-2-propenyl)- ω -hydroxypoly(oxy-1,2-ethanediyl), graft (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

CMF C13 H7 F17 O2

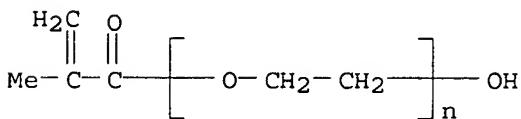


CM 2

CRN 25736-86-1

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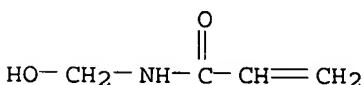
CCI PMS



CM 3

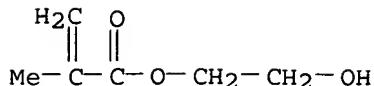
CRN 924-42-5

CMF C4 H7 N O2



CM 4

CRN 868-77-9



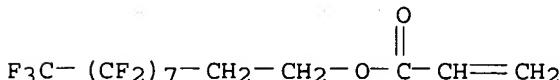
L19 ANSWER 6 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2002:45669 USPATFULL
 TITLE: Top coating for synthetic leathers
 INVENTOR(S): Huang, Hsu-Nan, Newark, DE, United States
 PATENT ASSIGNEE(S): E. I. du Pont de Nemours and Company, Wilmington, DE,
 United States (U.S. corporation)

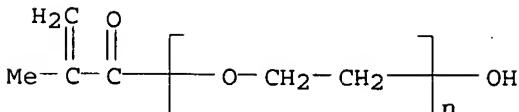
| | NUMBER | KIND | DATE |
|---------------------|----------------|------|--------------|
| PATENT INFORMATION: | US 6353051 | B1 | 20020305 |
| APPLICATION INFO.: | US 2000-495132 | | 20000131 (9) |

| | NUMBER | DATE |
|--|---|--|
| PRIORITY INFORMATION: | US 1999-123601P | 19990310 (60) |
| DOCUMENT TYPE: | Utility | |
| FILE SEGMENT: | GRANTED | |
| PRIMARY EXAMINER: | Yoon, Tae H. | |
| NUMBER OF CLAIMS: | 9 | |
| EXEMPLARY CLAIM: | 1 | |
| NUMBER OF DRAWINGS: | 0 Drawing Figure(s); 0 Drawing Page(s) | |
| LINE COUNT: | 1019 | |
| CAS INDEXING IS AVAILABLE FOR THIS PATENT. | | |
| IT | 292849-59-3P | (water- and oil-repellent coating compns. for synthetic grain leather) |
| RN | 292849-59-3 | USPATFULL |
| CN | 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, N-(hydroxymethyl)-2-propenamide and α -(2-methyl-1-oxo-2-propenyl)- ω -hydroxypoly(oxy-1,2-ethanediyl), graft (9CI) (CA INDEX NAME) | |

CM 1

CRN 27905-45-9
CMF C13 H7 F17 O2

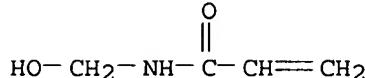
CM 2

CRN 25736-86-1
CMF (C₂ H₄ O)_n C₄ H₆ O₂
CCI PMS

CM 3

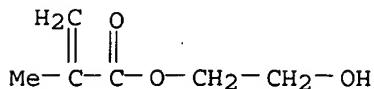
CRN 924-42-5

CMF C4 H7 N 02



CM 4

CRN 868-77-9
CMF C6 H10 O3



=> d his

(FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

L1 SCREEN 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 50 S L3 SSS SAM
L5 SCREEN 970 AND 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 39 S L7 SSS SAM
L9 SCREEN 970 AND 2067
L10 STRUCTURE UPLOADED
L11 QUE L10 AND L9
L12 19 S L11 SSS SAM
L13 102 S L4 OR L8 OR L12

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 20:41:37 ON 17 SEP 2004

L14 238 S L13
L15 130 DUPLICATE REMOVE L14 (108 DUPLICATES REMOVED)
L16 301 S OXIME SULFONATE
L17 3 S L16 AND L14
L18 9 S L14 AND (RESIST OR PHOTORESIST)
L19 6 S L18 NOT L17

=> exit y

| COST IN U.S. DOLLARS | SINCE FILE ENTRY | TOTAL SESSION |
|----------------------|------------------|---------------|
| FULL ESTIMATED COST | 52.86 | 54.75 |

STN INTERNATIONAL LOGOFF AT 20:45:24 ON 17 SEP 2004

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1752YXC

PASSWORD:

TERMINAL (ENTER 1, 2, 3, OR ?):2

* * * * * * * * * * * Welcome to STN International * * * * * * * * *

NEWS 1 Web Page URLs for STN Seminar Schedule - N. America
NEWS 2 "Ask CAS" for self-help around the clock
NEWS 3 May 12 EXTEND option available in structure searching
NEWS 4 May 12 Polymer links for the POLYLINK command completed in REGISTRY
NEWS 5 May 27 New UPM (Update Code Maximum) field for more efficient patent SDIs in CAplus
NEWS 6 May 27 CAplus super roles and document types searchable in REGISTRY
NEWS 7 Jun 28 Additional enzyme-catalyzed reactions added to CASREACT
NEWS 8 Jun 28 ANTE, AQUALINE, BIOENG, CIVILENG, ENVIROENG, MECHENG, and WATER from CSA now available on STN(R)
NEWS 9 Jul 12 BEILSTEIN enhanced with new display and select options, resulting in a closer connection to BABS
NEWS 10 Jul 30 BEILSTEIN on STN workshop to be held August 24 in conjunction with the 228th ACS National Meeting
NEWS 11 AUG 02 IFIPAT/IFIUDB/IFICDB reloaded with new search and display fields
NEWS 12 AUG 02 CAplus and CA patent records enhanced with European and Japan Patent Office Classifications
NEWS 13 AUG 02 STN User Update to be held August 22 in conjunction with the 228th ACS National Meeting
NEWS 14 AUG 02 The Analysis Edition of STN Express with Discover! (Version 7.01 for Windows) now available
NEWS 15 AUG 04 Pricing for the Save Answers for SciFinder Wizard within STN Express with Discover! will change September 1, 2004
NEWS 16 AUG 27 BIOPCOMMERCE: Changes and enhancements to content coverage
NEWS 17 AUG 27 BIOTECHABS/BIOTECHDS: Two new display fields added for legal status data from INPADOC
NEWS 18 SEP 01 INPADOC: New family current-awareness alert (SDI) available
NEWS 19 SEP 01 New pricing for the Save Answers for SciFinder Wizard within STN Express with Discover!
NEWS 20 SEP 01 New display format, HITSTR, available in WPIDS/WPINDEX/WPIX
NEWS 21 SEP 14 STN Patent Forum to be held October 13, 2004, in Iselin, NJ

NEWS EXPRESS JULY 30 CURRENT WINDOWS VERSION IS V7.01, CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP), AND CURRENT DISCOVER FILE IS DATED 11 AUGUST 2004
NEWS HOURS STN Operating Hours Plus Help Desk Availability
NEWS INTER General Internet Information
NEWS LOGIN Welcome Banner and News Items
NEWS PHONE Direct Dial and Telecommunication Network Access to STN
NEWS WWW CAS World Wide Web Site (general information)

Enter NEWS followed by the item number or name to see news on that specific topic.

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* * * * * * * * * * * STN Columbus * * * * * * * * * * * * * * *

FILE 'HOME' ENTERED AT 20:47:48 ON 17 SEP 2004

=>Testing the current file.... screen

THIS COMMAND NOT AVAILABLE IN THE CURRENT FILE

Please change to a suitable file and repeat your upload

Some commands only work in certain files. For example, the EXPAND command can only be used to look at the index in a file which has an index. Enter "HELP COMMANDS" at an arrow prompt (=>) for a list of commands which can be used in this file.

```
=> file reg
COST IN U.S. DOLLARS
FULL ESTIMATED COST
```

| | SINCE FILE
ENTRY | TOTAL
SESSION |
|--|---------------------|------------------|
| | 0.21 | 0.21 |

FILE 'REGISTRY' ENTERED AT 20:48:21 ON 17 SEP 2004
 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
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 COPYRIGHT (C) 2004 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file
 provided by InfoChem.

STRUCTURE FILE UPDATES: 16 SEP 2004 HIGHEST RN 746205-18-5
 DICTIONARY FILE UPDATES: 16 SEP 2004 HIGHEST RN 746205-18-5

TSCA INFORMATION NOW CURRENT THROUGH MAY 21, 2004

Please note that search-term pricing does apply when
 conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more
 information enter HELP PROP at an arrow prompt in the file or refer
 to the file summary sheet on the web at:
<http://www.cas.org/ONLINE/DBSS/registryss.html>

=>Testing the current file.... screen

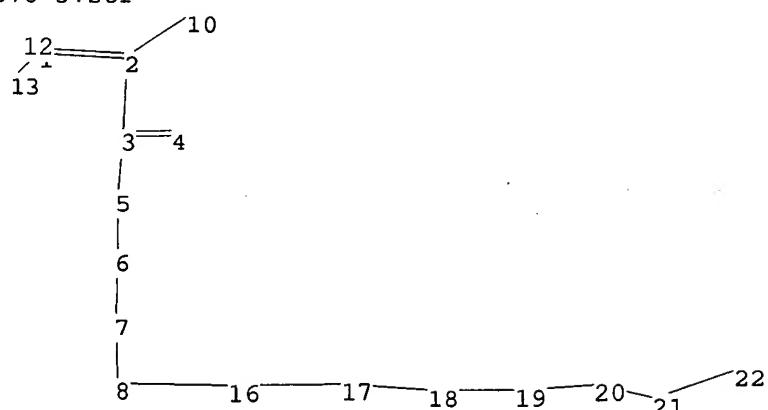
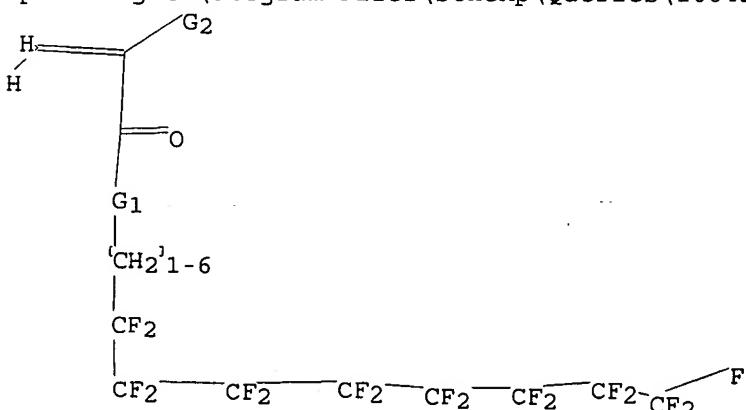
ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L1 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10642576-3.str



chain nodes :

1 2 3 4 5 6 7 8 10 12 13 16 17 18 19 20 21 22

chain bonds :

1-2 1-12 1-13 2-3 2-10 3-4 3-5 5-6 6-7 7-8 8-16 16-17 17-18 18-19 19-20 20-21

21-22

exact/norm bonds :

2-10 3-4 3-5 5-6

exact bonds :

1-2 1-12 1-13 2-3 6-7 7-8 8-16 16-17 17-18 18-19 19-20 20-21 21-22

G1:O,S,N

G2:CH2,H

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 12:CLASS
13:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS 20:CLASS 21:CLASS 22:CLASS

L2 STRUCTURE UPLOADED

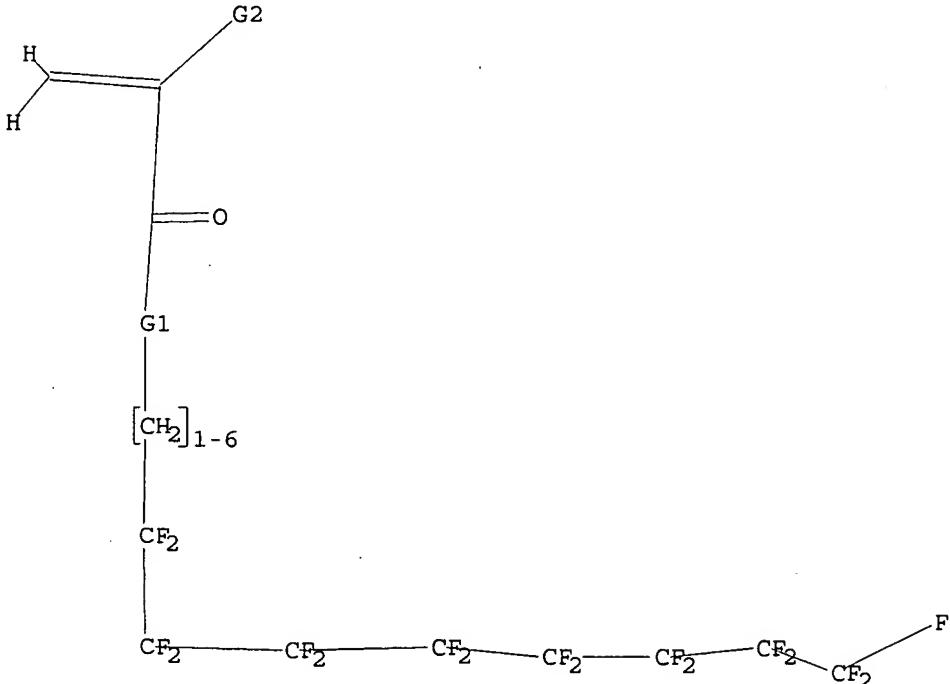
=> que L2 AND L1

L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 970 AND 2067
L2 STR



G1 O,S,N

G2 CH2,H

Structure attributes must be viewed using STN Express query preparation.

L3 QUE ABB=ON PLU=ON L2 AND L1

=> s 13

SAMPLE SEARCH INITIATED 20:48:59 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 350 TO ITERATE

100.0% PROCESSED 350 ITERATIONS

50 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 5878 TO 8122
PROJECTED ANSWERS: 2990 TO 4648

L4 50 SEA SSS SAM L2 AND L1

=> FIL HCAPLUS, CAPLUS, USPATFULL

| COST IN U.S. DOLLARS | SINCE FILE ENTRY | TOTAL SESSION |
|----------------------|------------------|---------------|
| FULL ESTIMATED COST | 0.42 | 0.63 |

FILE 'HCAPLUS' ENTERED AT 20:49:07 ON 17 SEP 2004

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FILE 'CAPLUS' ENTERED AT 20:49:07 ON 17 SEP 2004

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
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FILE 'USPATFULL' ENTERED AT 20:49:07 ON 17 SEP 2004

CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 14 and (oxime sulfonate)

L5 3 L4 AND (OXIME SULFONATE)

=> d 15 1-3 ibib

L5 ANSWER 1 OF 3 HCAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2004:200910 HCAPLUS

DOCUMENT NUMBER: 140:243596

TITLE: Chemically amplified positive photoresists suppressing development defects

INVENTOR(S): Momota, Atsushi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|--------|------------|-----------------|------------|
| JP 2004078105 | A2 | 20040311 | JP 2002-241946 | 20020822 |
| US 2004048190 | A1 | 20040311 | US 2003-642576 | 20030819 |
| PRIORITY APPLN. INFO.: | | | JP 2002-241946 | A 20020822 |
| OTHER SOURCE(S): | MARPAT | 140:243596 | | |

L5 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2004:200910 CAPLUS

DOCUMENT NUMBER: 140:243596

TITLE: Chemically amplified positive photoresists suppressing development defects

INVENTOR(S): Momota, Atsushi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|------|----------|-----------------|------------|
| JP 2004078105 | A2 | 20040311 | JP 2002-241946 | 20020822 |
| US 2004048190 | A1 | 20040311 | US 2003-642576 | 20030819 |
| PRIORITY APPLN. INFO.: | | | JP 2002-241946 | A 20020822 |

OTHER SOURCE(S) :

MARPAT 140:243596

L5 ANSWER 3 OF 3 USPATFULL on STN
ACCESSION NUMBER: 2004:63672 USPATFULL
TITLE: Positive photoresist composition
INVENTOR(S): Momota, Makoto, Shizuoka, JAPAN
PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

| | NUMBER | KIND | DATE |
|---------------------|----------------|------|---------------|
| PATENT INFORMATION: | US 2004048190 | A1 | 20040311 |
| APPLICATION INFO.: | US 2003-642576 | A1 | 20030819 (10) |

| | NUMBER | DATE |
|--|--|----------|
| PRIORITY INFORMATION: | JP 2002-241946 | 20020822 |
| DOCUMENT TYPE: | Utility | |
| FILE SEGMENT: | APPLICATION | |
| LEGAL REPRESENTATIVE: | SUGHRUE MION, PLLC, 2100 PENNSYLVANIA AVENUE, N.W.,
WASHINGTON, DC, 20037 | |
| NUMBER OF CLAIMS: | 8 | |
| EXEMPLARY CLAIM: | 1 | |
| LINE COUNT: | 1349 | |
| CAS INDEXING IS AVAILABLE FOR THIS PATENT. | | |

=> d his

(FILE 'HOME' ENTERED AT 20:47:48 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:48:21 ON 17 SEP 2004

L1 SCREEN 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 50 S L3

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 20:49:07 ON 17 SEP 2004
L5 3 S L4 AND (OXIME SULFONATE)

=> s 14 and (resist or photoresist)
L6 9 L4 AND (RESIST OR PHOTORESIST)

=> s 16 not 15
L7 6 L6 NOT L5

=> d 17 1-6 cit
'CIT' IS NOT A VALID FORMAT
In a multifile environment, a format can only be used if it is valid
in at least one of the files. Refer to file specific help messages
or the STNGUIDE file for information on formats available in
individual files.

REENTER DISPLAY FORMAT FOR ALL FILES (FILEDEFAULT):ibib

L7 ANSWER 1 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2003:735196 HCAPLUS
DOCUMENT NUMBER: 139:267983
TITLE: Positive-working photoresist composition
INVENTOR(S): Fujimori, Toru
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------|-------|-------|-----------------|-------|
| ----- | ----- | ----- | ----- | ----- |

JP 2003262952 A2 20030919 JP 2002-65444 20020311
PRIORITY APPLN. INFO.: 1998:335551 CAPLUS 2002-65444 20020311

L7 ANSWER 2 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1998:335551 CAPLUS
DOCUMENT NUMBER: 129:54119
TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their (polymer) films, and photoresists using the same
INVENTOR(S): Miyashita, Tokuji
PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|------|------------------|-----------------|----------|
| JP 10139747 | A2 | 19980526 | JP 1996-312953 | 19961108 |
| PRIORITY APPLN. INFO.: | | | JP 1996-312953 | 19961108 |
| OTHER SOURCE(S): | | MARPAT 129:54119 | | |

L7 ANSWER 3 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2003:735196 CAPLUS
DOCUMENT NUMBER: 139:267983
TITLE: Positive-working photoresist composition containing polymer with fluoro-aliphatic group
INVENTOR(S): Fujimori, Toru
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|------|----------|-----------------|----------|
| JP 2003262952 | A2 | 20030919 | JP 2002-65444 | 20020311 |
| PRIORITY APPLN. INFO.: | | | JP 2002-65444 | 20020311 |

L7 ANSWER 4 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1998:335551 CAPLUS
DOCUMENT NUMBER: 129:54119
TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their (polymer) films, and photoresists using the same
INVENTOR(S): Miyashita, Tokuji
PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|------|------------------|-----------------|----------|
| JP 10139747 | A2 | 19980526 | JP 1996-312953 | 19961108 |
| PRIORITY APPLN. INFO.: | | | JP 1996-312953 | 19961108 |
| OTHER SOURCE(S): | | MARPAT 129:54119 | | |

L7 ANSWER 5 OF 6 USPATFULL on STN
ACCESSION NUMBER: 2002:59638 USPATFULL
TITLE: Top coating for synthetic leathers
INVENTOR(S): Huang, Hsu-Nan, Newark, DE, UNITED STATES

| | NUMBER | KIND | DATE |
|-----------------------|--|------|--------------|
| PATENT INFORMATION: | US 2002033468 | A1 | 20020321 |
| APPLICATION INFO.: | US 2001-970478 | A1 | 20011004 (9) |
| RELATED APPLN. INFO.: | Division of Ser. No. US 2000-495132, filed on 31 Jan 2000, PENDING | | |

| | NUMBER | DATE |
|--|---|---------------|
| PRIORITY INFORMATION: | US 1999-123601P | 19990310 (60) |
| DOCUMENT TYPE: | Utility | |
| FILE SEGMENT: | APPLICATION | |
| LEGAL REPRESENTATIVE: | E I DU PONT DE NEMOURS AND COMPANY, LEGAL DEPARTMENT - PATENTS, 1007 MARKET STREET, WILMINGTON, DE, 19898 | |
| NUMBER OF CLAIMS: | 11 | |
| EXEMPLARY CLAIM: | 1 | |
| LINE COUNT: | 1042 | |
| CAS INDEXING IS AVAILABLE FOR THIS PATENT. | | |

L7 ANSWER 6 OF 6 USPATFULL on STN
 ACCESSION NUMBER: 2002:45669 USPATFULL
 TITLE: Top coating for synthetic leathers
 INVENTOR(S): Huang, Hsu-Nan, Newark, DE, United States
 PATENT ASSIGNEE(S): E. I. du Pont de Nemours and Company, Wilmington, DE, United States (U.S. corporation)

| | NUMBER | KIND | DATE |
|---------------------|----------------|------|--------------|
| PATENT INFORMATION: | US 6353051 | B1 | 20020305 |
| APPLICATION INFO.: | US 2000-495132 | | 20000131 (9) |

| | NUMBER | DATE |
|--|--|---------------|
| PRIORITY INFORMATION: | US 1999-123601P | 19990310 (60) |
| DOCUMENT TYPE: | Utility | |
| FILE SEGMENT: | GRANTED | |
| PRIMARY EXAMINER: | Yoon, Tae H. | |
| NUMBER OF CLAIMS: | 9 | |
| EXEMPLARY CLAIM: | 1 | |
| NUMBER OF DRAWINGS: | 0 Drawing Figure(s); 0 Drawing Page(s) | |
| LINE COUNT: | 1019 | |
| CAS INDEXING IS AVAILABLE FOR THIS PATENT. | | |

| COST IN U.S. DOLLARS | SINCE FILE ENTRY | TOTAL SESSION |
|----------------------|------------------|---------------|
| FULL ESTIMATED COST | 22.55 | 23.18 |

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